PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Yuan-Hsun WU

Filed: 9/8/2003

Appl. No.: 10/657,789

Examiner: RUGGLES, JOHN

Conf. No.: 1374

Art Unit:

Title: PHOTOMASK STRUCTURE AND METHOD OF REDUCING LENS

ABERRATION AND PATTERN DISPLACEMENT

Date: January 9, 2006

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

FACSIMILE COVER SHEET

Attached hereto please find the following papers filed in connection with the above identified application:

- 1) Response to Restriction Requirement; and
- 2) Preliminary Amendment.

No fee is believed to be due in connection with the filing of these papers. If, however, the Commissioner considers that a fee is due in connection with the filing of these papers, authorization is made to charge any fee which may be required to Deposit Account No. 502447.

P114934NAQ

PATENT

Certificate Transmission

I hereby certify that this correspondence is being facsimile transmitted to the United States Patent & Trademark Office to (571) 273-8300 on the date shown below:

Nelson A. Quintero

(Name of Person Transmitting)

(Signature)

January 9, 2006

(Date)

Respectfully submitted,

Nelson A. Quintero

Attorney for Applicant

Reg. No. 52,143

Customer No. 34,283

Telephone:

(310) 401-6180

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Yuan-Hsun WU

Filed: 9/8/2003

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Appl. No.: 10/657,789

Examiner: RUGGLES, JOHN

JAN 0 9 2006

Conf. No.: 1374

Art Unit: 1756

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Title: PHOTOMASK STRUCTURE AND METHOD OF REDUCING LENS

ABERRATION AND PATTERN DISPLACEMENT

Date: January 9, 2006

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Sir:

Responsive to the restriction requirement mailed on December 27, 2005, Applicant hereby elects the invention of Group I (claims 1-6) for examination, without traverse. This election is made without prejudice to Applicant's right to file divisional applications directed to the non-elected inventions. A prompt and favorable action on the merits of this application is now respectfully requested.

No fee is believed to be due in connection with this response. If, however, the Commissioner considers that a fee is due in connection with this response, authorization is made to charge any fee which may be required to Deposit Account No. <u>502447</u>.

Certificate of Transmission Respectfully submitted, I hereby certify that this correspondence is being facsimile transmitted to the United States Patent & Trademark Office to (571) 273-8300 on the date shown below: Nelson A. Quintero Nelson A. Quintero (Name of Person Transmitting) Attorney for Applicant Reg. No. 52,143 (Signature) Customer No. 34,283 January 9, 2006 Telephone: (310) 401-6180 (Date)

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PATENT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Yuan-Hsun WU

Filed: 9/8/2003

CENTRAL FAX CENTRE

Appl. No.: 10/657,789

Examiner: RUGGLES, JOHN

LAN & A

Conf. No.: 1374

Art Unit: 1756

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Title: PHOTOMASK STRUCTURE AND METHOD OF REDUCING LENS

ABERRATION AND PATTERN DISPLACEMENT

Date: January 9, 2006

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

AMENDMENT

Sir:

The Office Action mailed on **January 9, 2006** has been carefully considered. In response thereto, the Applicant respectfully requests entry of the amendments and consideration of the remarks as set forth herein below:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks begin on page 4 of this paper.

All amendments and remarks made herein are without prejudice.